

In the specification:

Please amend the last partial paragraph on page 3 beginning on line 20 and ending on line 6 of page 4 as follows:

The focusing elements may be any of a variety of diffractive and/or refractive elements including those disclosed in U.S. Patent Application Ser. No. [~~10/~~, ~~---~~] 10/624,316 filed July 22, 2003, (the disclosure of which is hereby incorporated by reference) which claims priority to U.S. Provisional Applications Ser. Nos. 60/397,705 and 60/404,514, including, for example, amplitude and/or phase Fresnel zone plates, blazed Fresnel zone plates, bessell zone plates, photon sieves (e.g., amplitude photon sieves, phase photon sieves, or alternating phase photon sieves), and the diffractive focusing elements may be apodized. These may be microfabricated in large arrays as well, and may be designed to compensate for wavefront characteristics in the radiation output from the source array to achieve, for example, the smallest possible focal spot.

Please amend the first full paragraph on page 5 as follows:

By selectively modulating [~~the~~] each of an array of energy (or light) sources, while scanning a substrate, one may create arbitrary patterns. Such a system may be extremely compact (integrated) and have very high resolution and throughput.